



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

: Confirmation No. 4175

Hideo HADA et al.

: Docket No. 2001-1787A

Serial No. 09/996,676

: Group Art Unit 1752

Filed November 30, 2001

: Examiner R. Ashton

POSITIVE-WORKING PHOTORESIST  
COMPOSITION

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JUN 26 2003  
TC 1700

DECLARATION

Assistant Commissioner for Patents,  
Washington, D.C.

Sir:

I, Nobue KANAKA, declare and say:

that I am thoroughly conversant in both the Japanese and English languages;

that I am presently engaged as a translator in these languages;

that the attached document represents a true English translation of the Japanese Priority Application No. 2000-369225, filed December 4, 2000.

I further declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Signed this 12th day of June, 2003.

Nobue Kanaka  
Translator